

Thickness Dependence of Current-Induced Effective Magnetic Field in $\text{La}_{0.67}\text{Sr}_{0.33}\text{MnO}_3/\text{SrTiO}_3$ heterostructure

¹School of Eng., and ²RIES-Hokkaido Univ.

○Tatsuro Oyamada^{1*}, Takayoshi Katase², Hiromichi Ohta², and Michihiko Yamanouchi²

*E-mail: t-oyamada@eis.hokudai.ac.jp

Last year, we have reported that effective magnetic field H_{eff} can be induced by the application of in-plane current in an oxide half-metal heterostructure, $\text{La}_{0.67}\text{Sr}_{0.33}\text{MnO}_3/\text{SrTiO}_3$ [1]. In this study, we measured $\text{La}_{0.67}\text{Sr}_{0.33}\text{MnO}_3$ (LSMO) thickness dependence of H_{eff} to clarify the origin of the H_{eff} on LSMO.

PLD-grown LSMO films (13, 18 and 25 u.c.) on TiO_2 -terminated SrTiO_3 (001) substrates were processed into devices with Hall bar electrode geometry having a $w = 10\text{-}\mu\text{m}$ wide channel along [100]. Transverse resistance R_{yx} was measured under application of rotating external magnetic field H_{ext} in the plane. The in-plane angle ϕ -dependence of R_{yx} in the presense of a static H_{ext} indicates that all the LSMO films have an in-plane biaxial magnetic anisotropy with the easy axes almost along $\langle 110 \rangle$ (the hard axes almost along $\langle 100 \rangle$). After aligning magnetization direction by $\mu_0 H_{\text{ext}} = 0.5\text{ T}$ along $[\bar{1}10]$ at device temperature $T_d = 130\text{ K}$, we measured R_{yx} under various currents while rotating H_{ext} around one of hard axes $[\bar{1}00]$ in the counterclockwise direction. The magnitude of H_{ext} was seted larger than the magnetic anisotropy field to prevent domain nucleation. T_d was determined by using longitudinal resistance to correct Joule heating. Switching of magnetization direction under positive current occurs at larger ϕ compared with that under negative current, where positive (negative) current is directed along [100] ($[\bar{1}00]$). This behaviour is consistent with previous results: H_{eff} along [010] ($[\bar{0}10]$) is induced by positive (negative) current [1]. We evalutaed H_{eff} from the difference of switching angle [2]. Although thinner LSMO film exhibited large H_{eff} at lower current (Figure) , it was scaled with the effective current density, I/wt_{eff} , where $t_{\text{eff}} = \text{total LSMO thickness} - \text{dead layer thickness (6 u.c.)}$ [3], suggesting that the H_{eff} can be induced in LSMO bulk reagon.

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References

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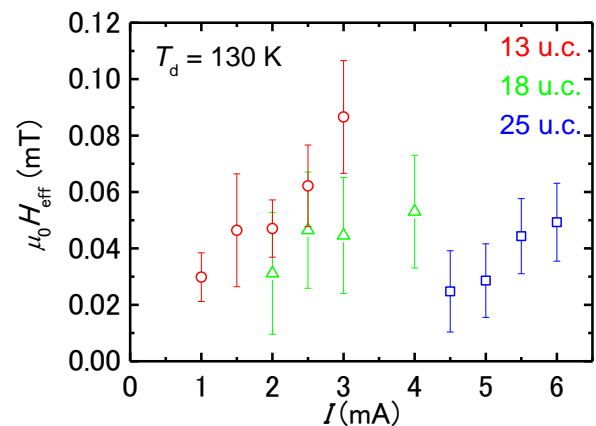


Figure: I -dependence of H_{eff}